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--This is a division of Application Serial No. 09/271,654, filed March 17, 1999.--

In the Claims:

Please cancel Claims 1-3, 9-11, 13-16, 20-51 and 59-61, without prejudice.

Marked-up versions of amended Claims 4-7 and 57 are provided in Attachment A, submitted herewith.

Please substitute the following for pending Claim 4:

H²
4. (Amended) A method of depositing a plurality of layers on an article, the method comprising steps of:

flowing a plasma gas in a plasma generation chamber in communication with a deposition chamber, the deposition chamber having a lower pressure than the plasma generation chamber, the article being disposed in the deposition chamber;

generating an arc in the plasma generation chamber to create a plasma, which flows into the deposition chamber;

injecting a first material comprising an organometallic material and a first oxidant into the plasma and reacting the first material to form an interlayer on the article, the interlayer comprising a polymerized organosilicon material; and

injecting a second material comprising an organosilicon material and a second oxidant into the plasma and reacting the second material to form a second layer comprising an inorganic ultraviolet absorbing material on the interlayer, the second material comprising a gaseous reagent, wherein the interlayer has a coefficient of thermal expansion that is between that of the substrate and the second layer.

Please substitute the following for pending Claim 5:

5. (Amended) The method of claim 4, wherein the first material or the second material comprises an evaporated elemental metal.

Please substitute the following for pending Claim 6:

6. (Amended) The method of claim 4, further comprising the step of injecting a third material into the plasma to form a third layer and reacting the third material to form a third layer comprising an abrasion resistant material on the second layer.

Please substitute the following for pending Claim 7:

7. (Amended) The method of claim 6, wherein the first material comprises a first organosilicon material, the second material comprises an evaporated elemental metal, and the third material comprises a third organosilicon material, and the method further comprises the step of injecting a third oxidant with the third material.

Please substitute the following for pending Claim 57:

A³ 57. (Amended) The method of claim 4, wherein the substrate comprises glass.

REMARKS

Applicants have submitted herewith a division of Serial No. 09/ Application Serial No. 09/271,654, filed March 17, 1999, and respectfully request that the accompanying Preliminary Amendment be entered. Claims 1-3, 9-11, 13-16, 20-51 and 59-61 have been canceled, without prejudice. As such, Claims 4-7, 12, 17-19, 52-58, and 62-73 remain in the case.